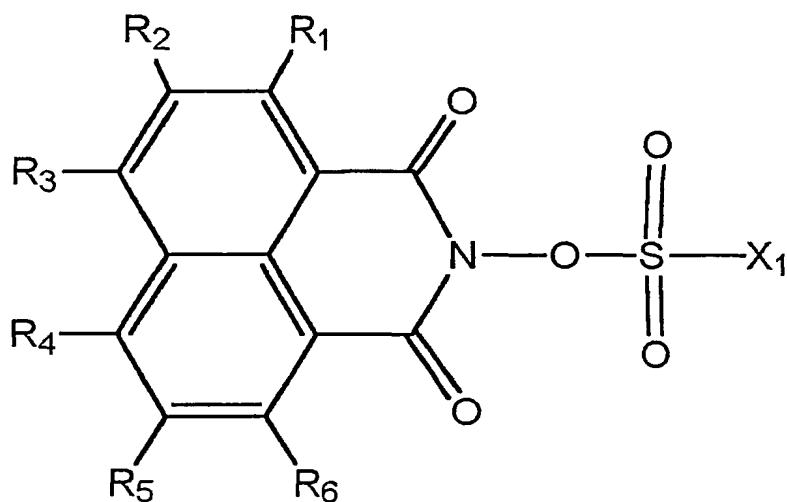


What is claimed is:

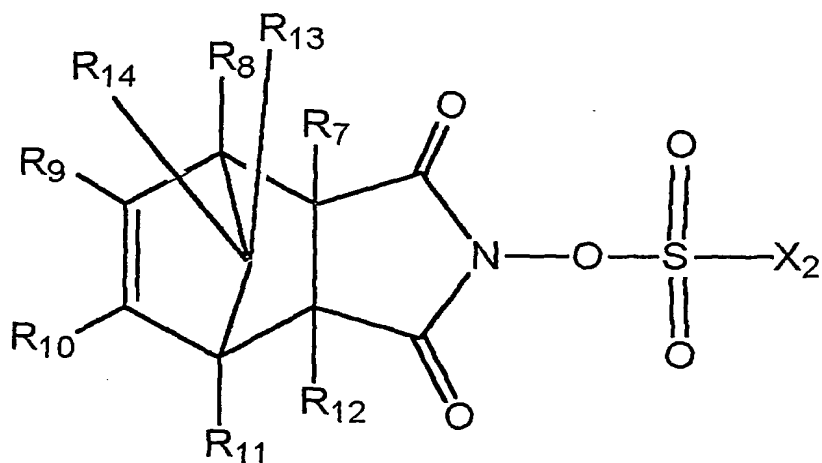
1. A positive working photosensitive composition comprising:
an epoxy compound having two or more epoxy groups in one molecule;
a curing catalyst or a compound for producing a curing catalyst by heat; and
sulfonates.

2. A composition according to Claim 1, wherein the sulfonates are at least one compound selected from the group consisting of a compound represented in the following formulae (1) to (7),



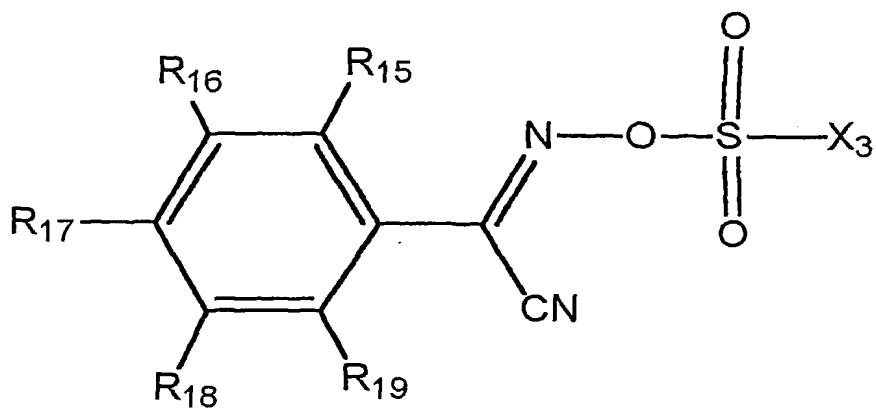
(1)

wherein X₁ is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R₁ to R₆ are each independently a hydrogen atom or a monovalent organic group,



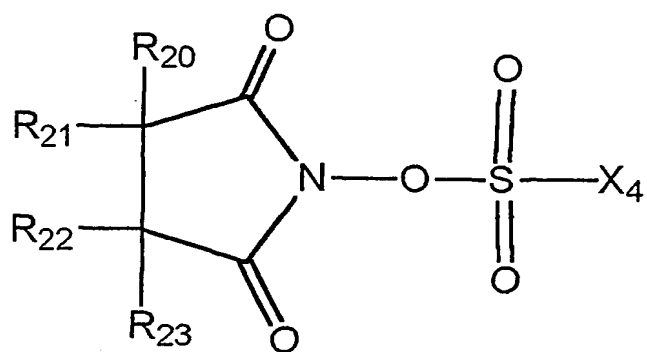
(2)

wherein X₂ is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R₇ to R₁₄ are each independently a hydrogen atom or a monovalent organic group,



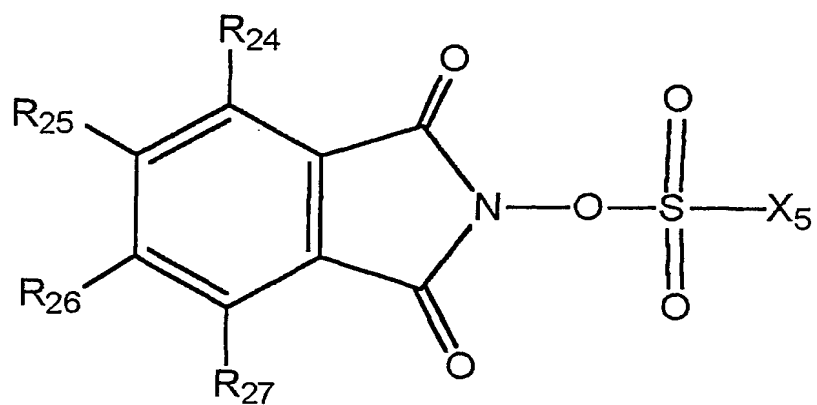
(3)

wherein X₃ is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R₁₅ to R₁₉ are each independently a hydrogen atom, an alkoxy group or a monovalent organic group,



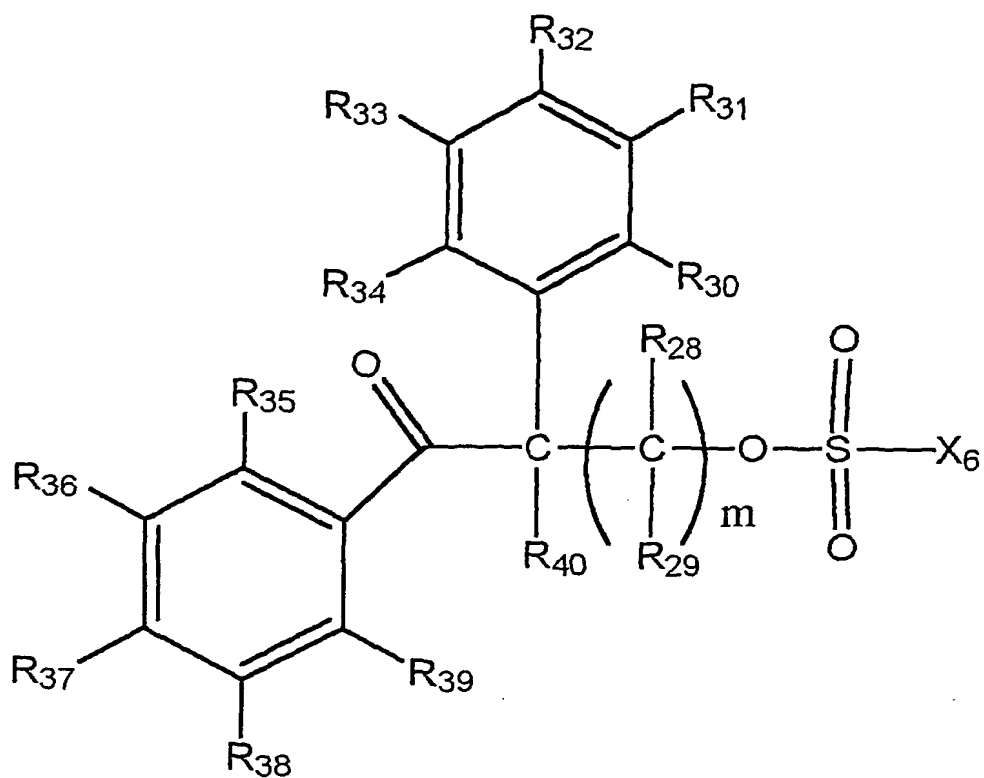
(4)

wherein X_4 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R_{20} to R_{23} are each independently a hydrogen atom or a monovalent organic group,



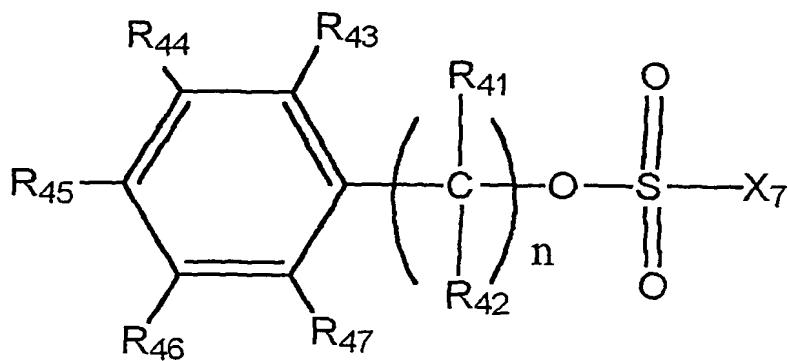
(5)

wherein X_5 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R_{24} to R_{27} are each independently a hydrogen atom or a monovalent organic group,



(6)

wherein X₆ is an optionally substituted monovalent organic group with a carbon number of 1 to 20, R₂₈ to R₃₉ are each independently a hydrogen atom or a monovalent organic group, R₄₀ is a hydrogen atom or a hydroxyl group, and m is 0 or 1,



(7)

wherein X_7 is an optionally substituted monovalent organic group, R_{41} and R_{42} are each independently a hydrogen atom or a monovalent organic group with a carbon number of 1 to 20, R_{43} to R_{47} are each independently a hydrogen atom, a nitro group or a monovalent organic group with a carbon number of 1 to 20, and n is 0 or 1.

3. A method of manufacturing a member for a semiconductor comprising the steps of:
applying a positive working photosensitive composition according to Claim 1 on a substrate to expose;
curing an unexposed part thereof by heat; and
developing an exposed part thereof.

4. A method of manufacturing a member for a display comprising the steps of:
applying a positive working photosensitive composition according to Claim 1 on a substrate to expose;
curing an unexposed part thereof by heat; and
developing an exposed part thereof.